

# **ECE606: Solid State Devices**

## **Lecture 34: MOSCAP Frequency Response**

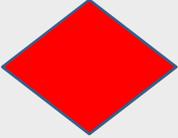
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# Outline

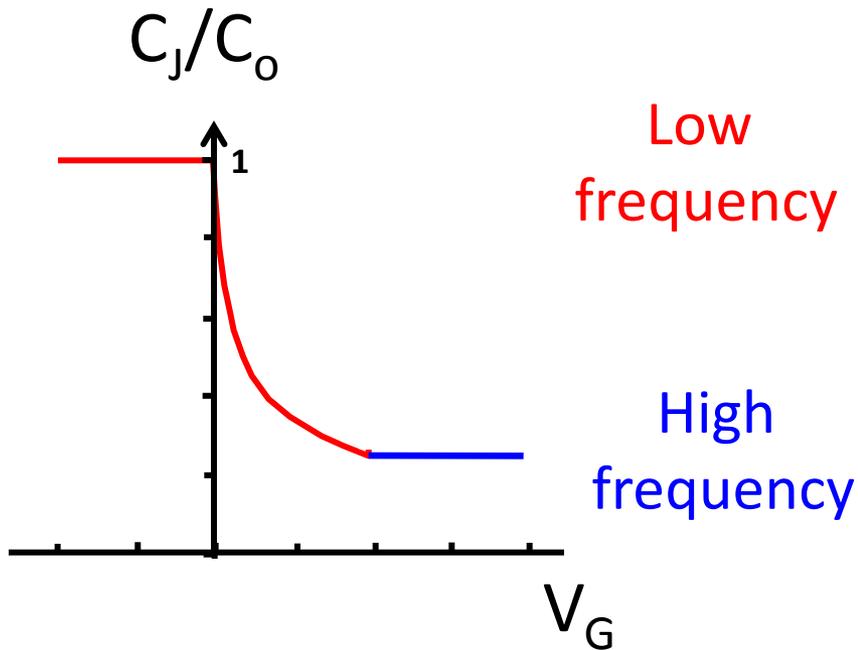
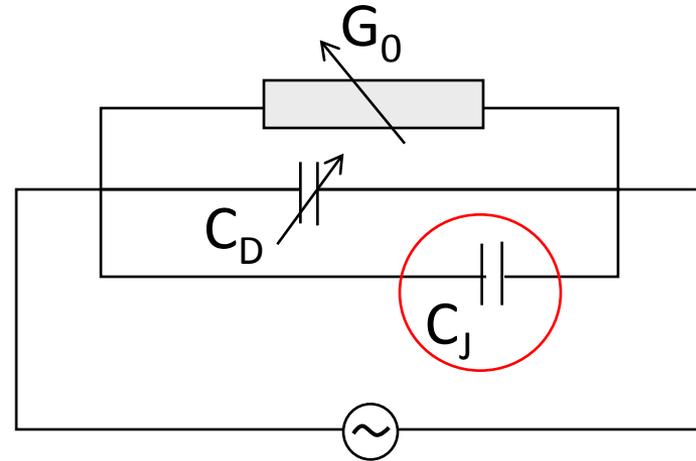
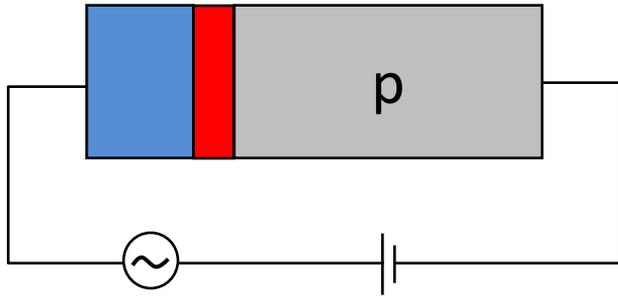
- 1. Background**
2. Small signal capacitances
3. Large signal capacitance
4. Conclusion

**Ref:** Sec. 16.4 of SDF

# Topic Map

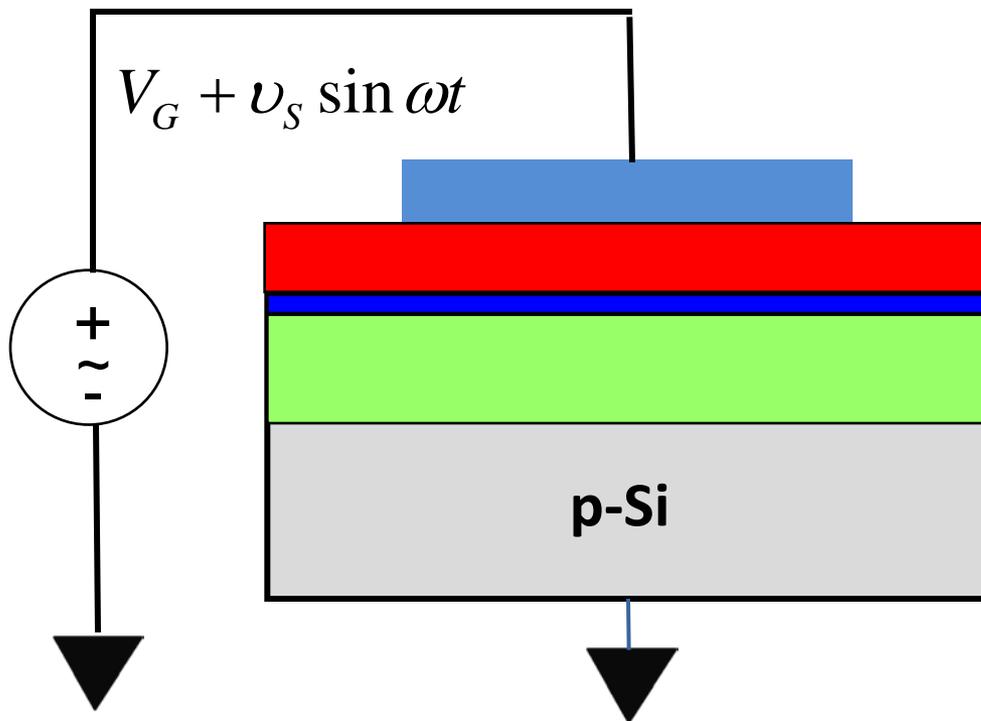
	Equilibrium	DC	<b>Small signal</b>	Large Signal	Circuits
Diode					
Schottky					
BJT/HBT					
<b>MOSCAP</b>					

# Small Signal Equivalent Circuit



For insulated devices, consider only majority carrier junction capacitance  $C_J$

# Junction Capacitance



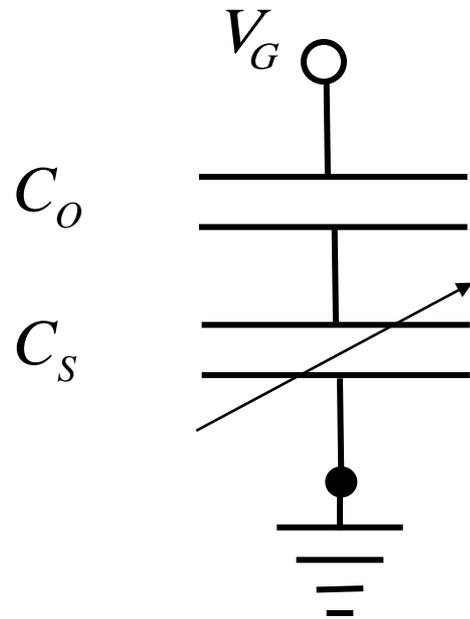
$$C_G \equiv \frac{dQ_G}{dV_G} = \frac{d(-Q_s)}{dV_G}$$

$$V_G = \psi_s - \frac{Q_s}{C_o}$$

$$\frac{dV_G}{d(-Q_s)} = \frac{d\psi_s}{d(-Q_s)} + \frac{1}{C_o}$$

$$\frac{1}{C_G} = \frac{1}{C_s} + \frac{1}{C_o}$$

# Junction Capacitance



which we already understand!

$$\frac{1}{C_G} = \frac{1}{C_s} + \frac{1}{C_o}$$

$$C_s \equiv \frac{d(-Q_s)}{d\psi_s}$$

$$Q_s(\psi_s)$$

# Definition of $m$ for later use

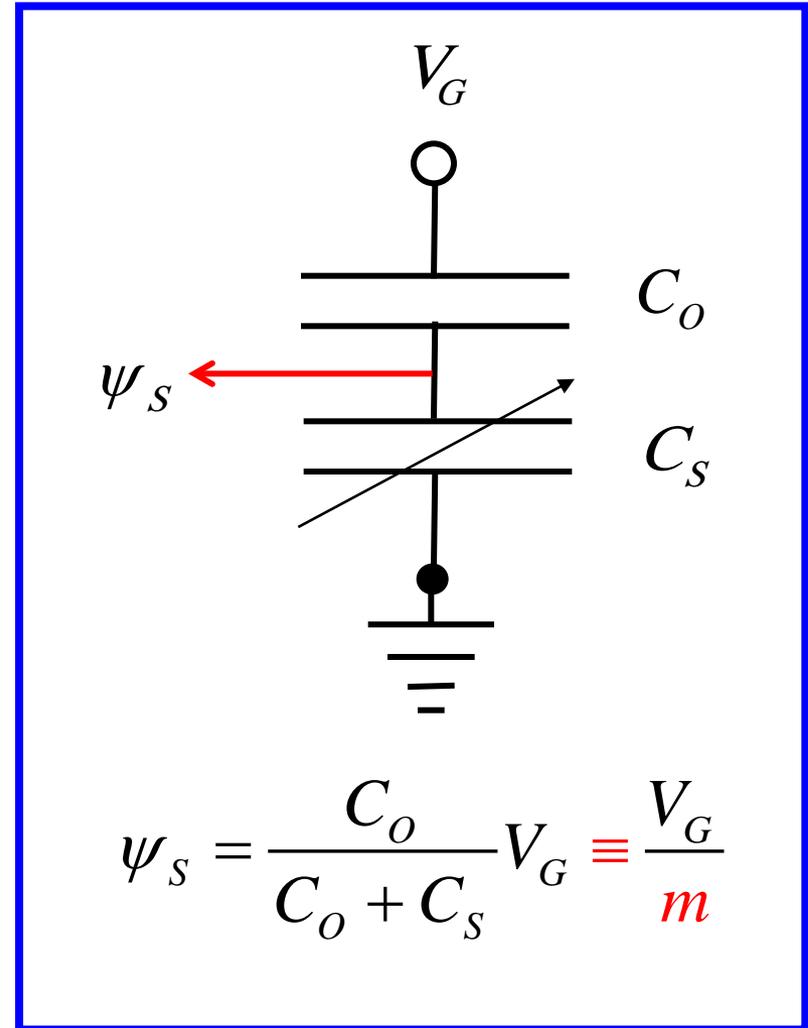
$$m = (1 + C_S / C_O)$$

'body effect coefficient'

$$m = (1 + \kappa_S x_O / \kappa_0 W_T)$$

in practice:

$$1.1 \leq m \leq 1.4$$



# Outline

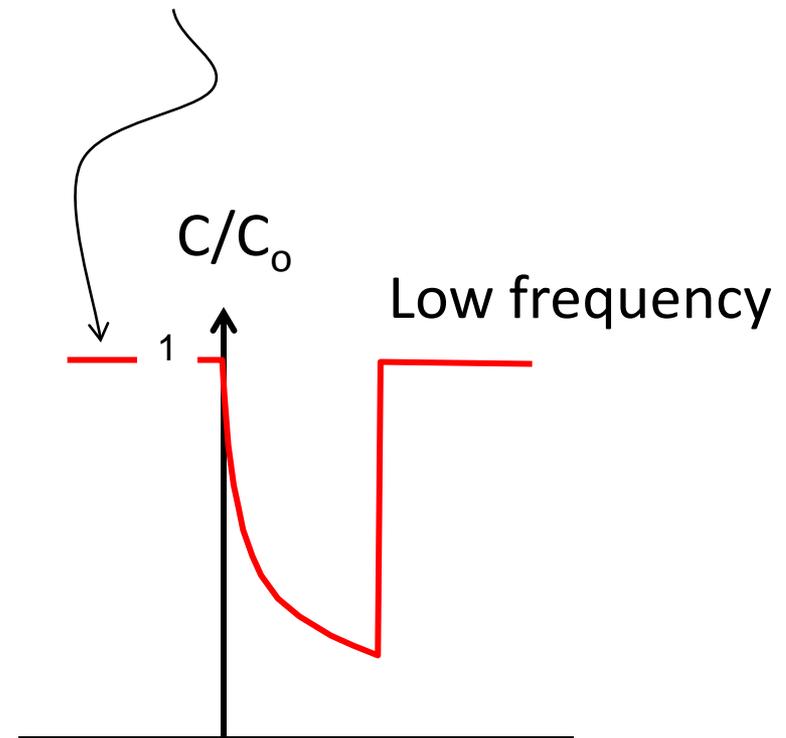
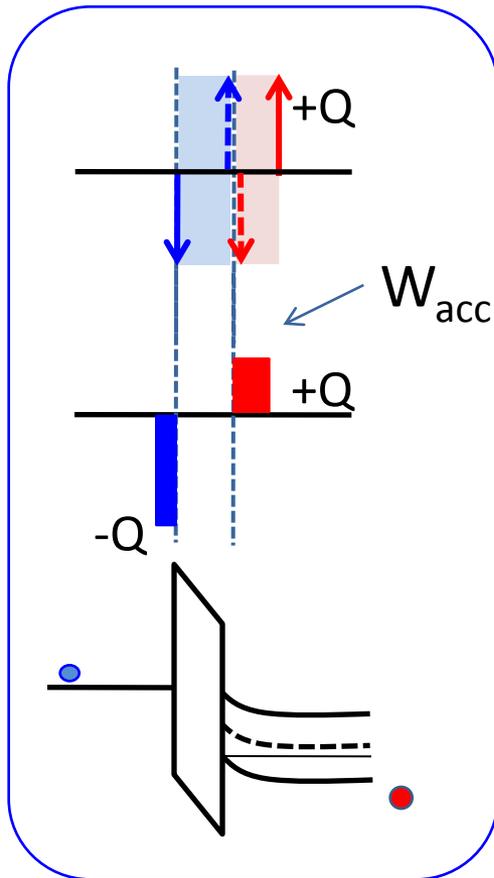
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# Junction Capacitance *in accumulation*

$$C_{j,acc} \approx \frac{K_{ox} \epsilon_0}{x_0} \equiv C_0$$

$$C_{j,acc} = \frac{C_o C_{s,acc}}{C_o + C_{s,acc}}$$

$$C_{s,acc} \equiv \frac{K_s \epsilon_0}{W_{acc}}$$



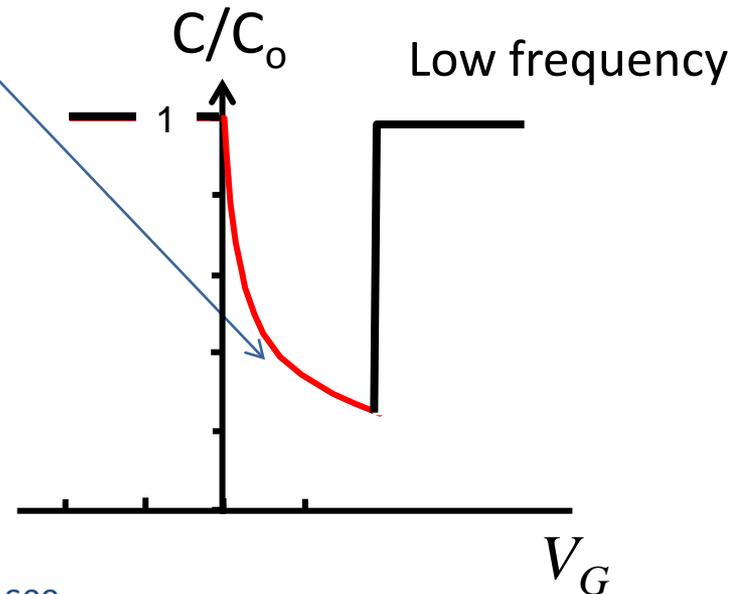
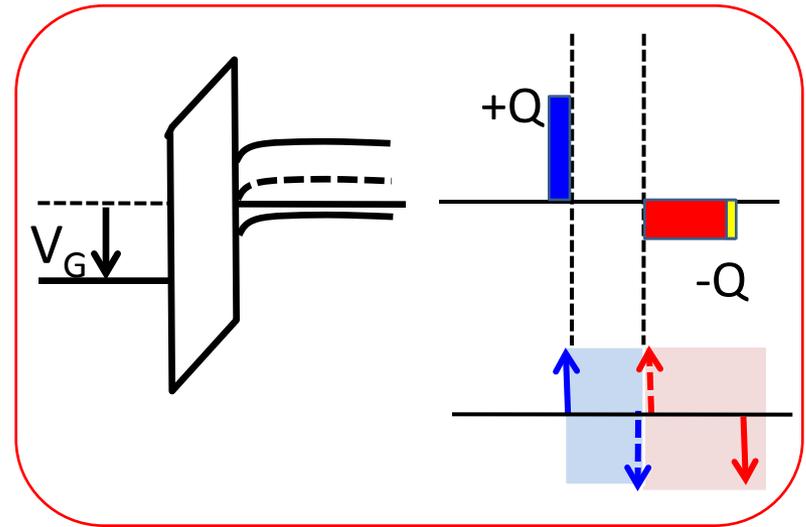
# Junction Capacitance *in depletion*

$$C_{j,dep} = \frac{C_0 C_s}{C_0 + C_s} = \frac{C_0}{1 + C_0/C_s}$$

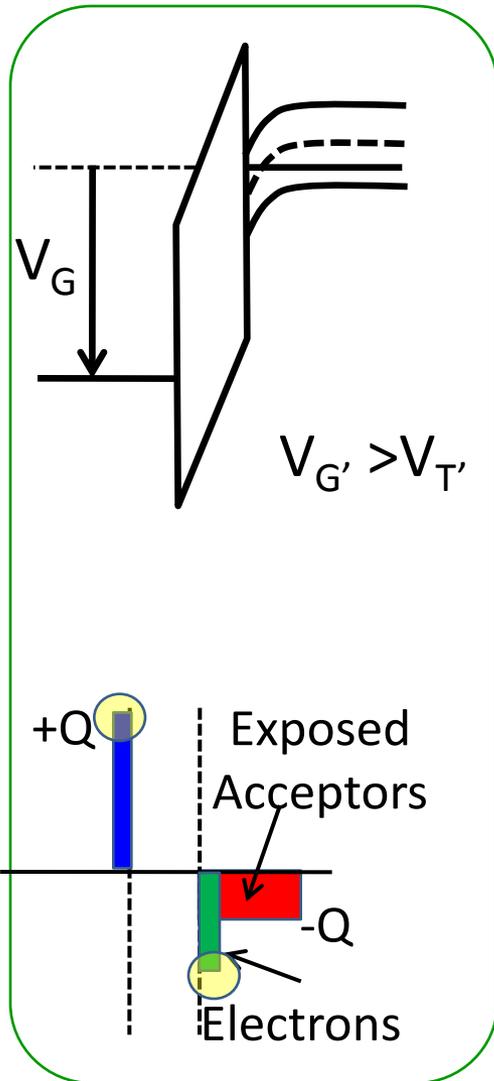
$$= \frac{C_0}{1 + \frac{\kappa_o \epsilon_0}{x_0} / \frac{\kappa_s \epsilon_0}{W}} = \frac{C_0}{\sqrt{1 + \frac{V_G}{V_\delta}}}$$

$$V_G = \frac{qN_A W}{\kappa_o \epsilon_0} x_0 + \left( \frac{qN_A W^2}{2\kappa_s \epsilon_0} \right)$$

$$\frac{\kappa_o W}{\kappa_s x_0} = \sqrt{1 + \frac{V_G}{V_\delta}} - 1$$

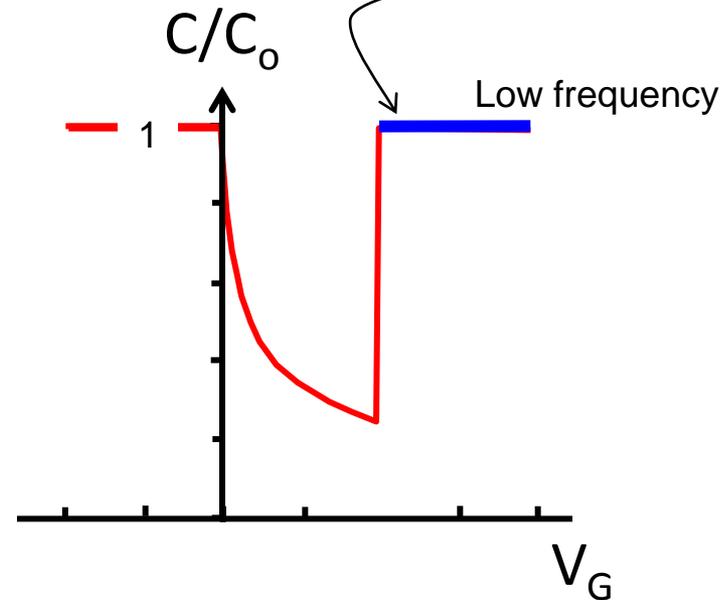


# Junction capacitance *in inversion*



$$C_{j,inv} \approx \frac{\kappa_s \epsilon_0}{x_0} \equiv C_0$$

$$C_{j,inv} = \frac{C_o C_{inv}}{C_o + C_{inv}} \quad C_{inv} \equiv \frac{\kappa_s \epsilon_0}{W_{inv}}$$



# Equivalent Oxide Thickness

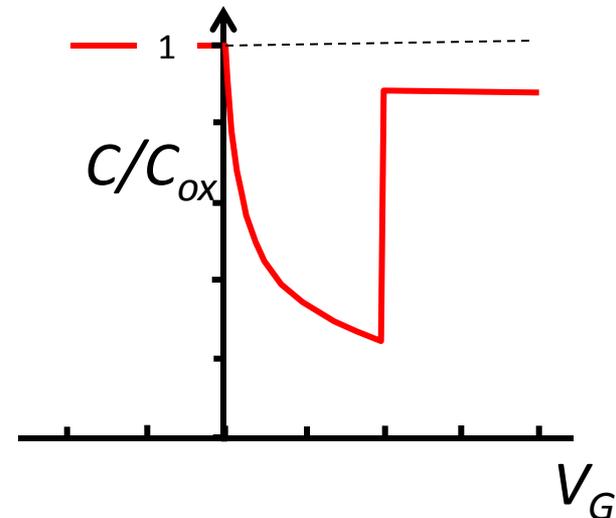
$$Q_i = -C_G (V_G - V_T)$$

$$C_G = C_{j,inv} = \frac{C_o C_{inv}}{C_{inv} + C_o} < C_o$$

$$C_o = \frac{\kappa_o \epsilon_o}{x_o} \quad C_{inv} \equiv \frac{\kappa_s \epsilon_o}{W_{inv}}$$

$$C_G = \frac{\kappa_{ox} \epsilon_o}{EOT_{elec}} \quad EOT_{elec} = x_o + \left( \frac{\kappa_{ox} \epsilon_o}{\kappa_s \epsilon_o} \right) W_{inv} > x_o$$

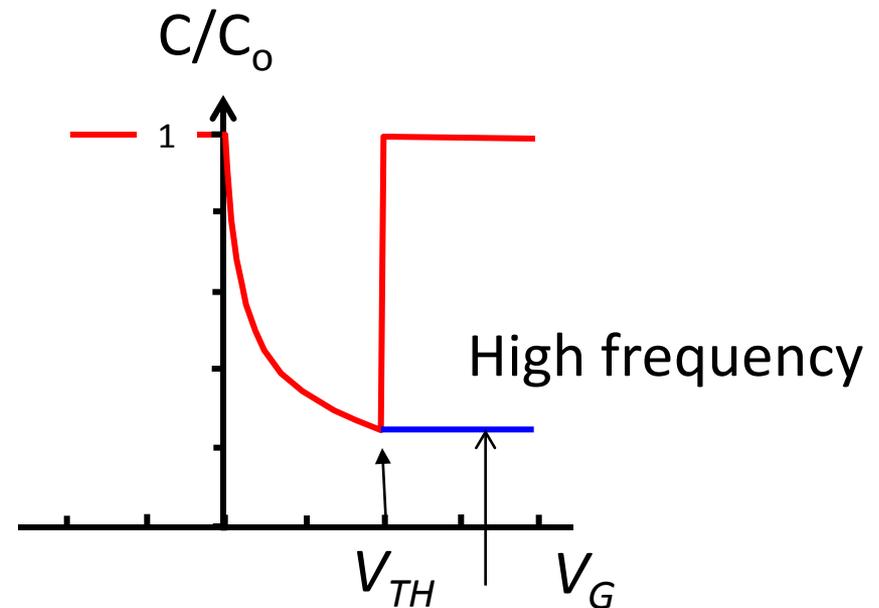
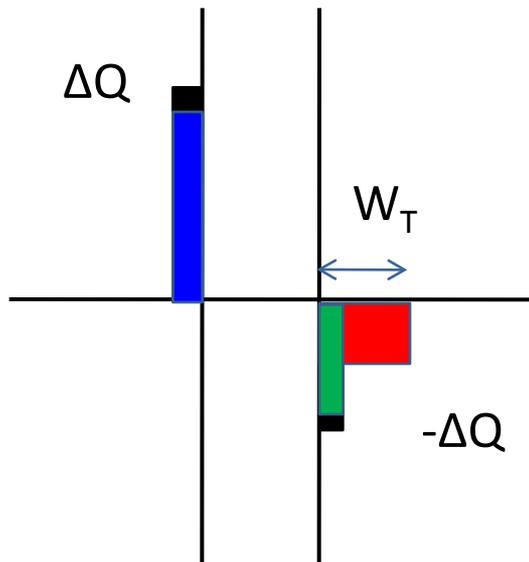
Low frequency



'Equivalent oxide thickness - electrical'

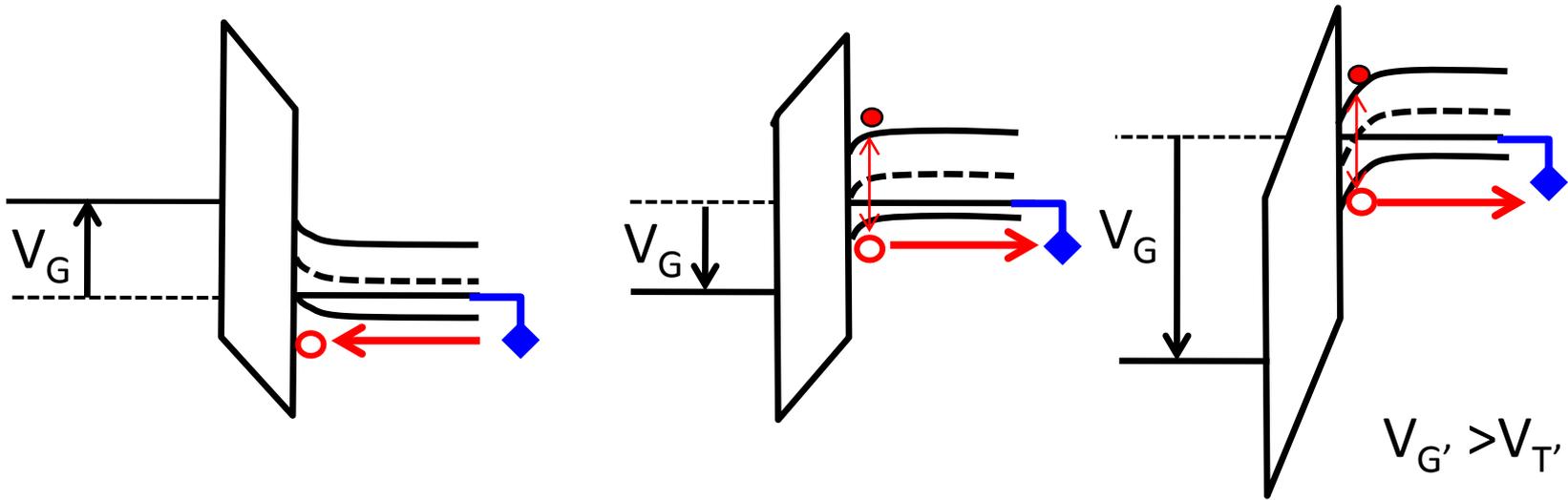
# High frequency curve at inversion

$$C_{j,inv} \approx \frac{K_s \epsilon_0}{x_0} \equiv C_0$$



What about high frequency part of the curve?

# Response Time



## Dielectric Relaxation

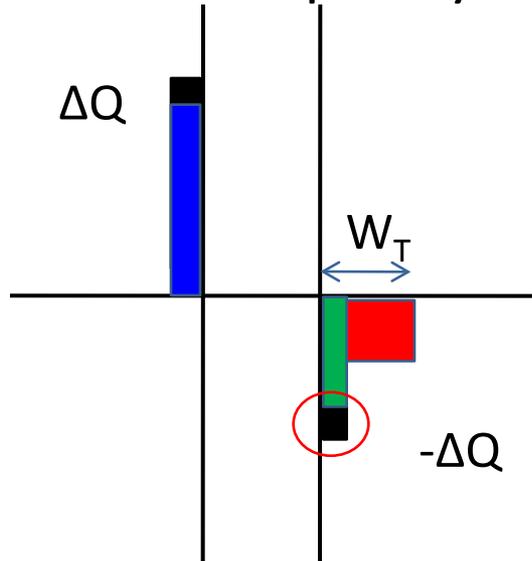
$$\tau = \frac{\sigma}{\kappa_s \epsilon_0}$$

## SRH Recombination-Generation

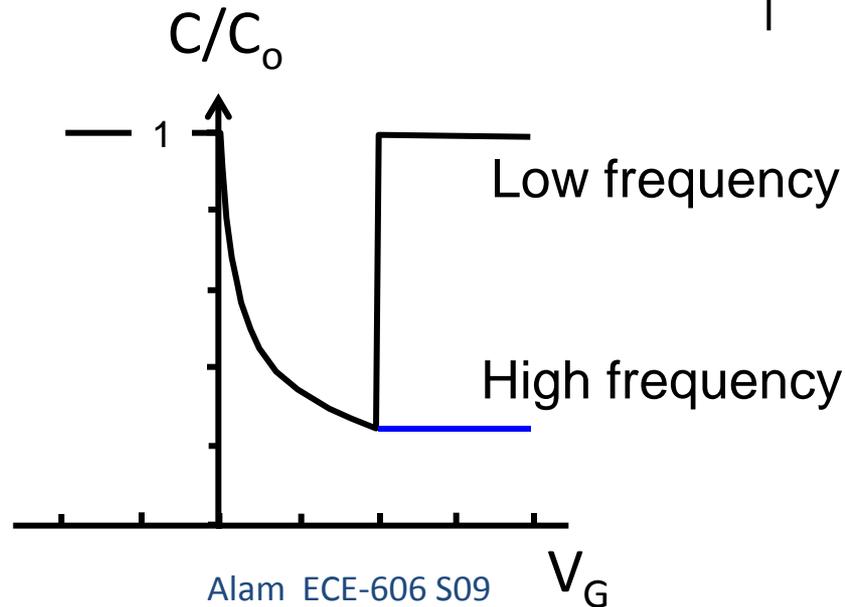
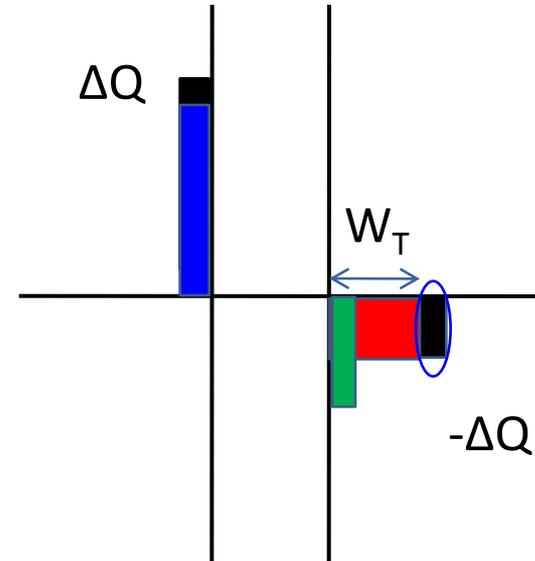
$$R = \frac{np - n_i^2}{\tau_n(p + p_1) + \tau_p(n + n_1)} \rightarrow \frac{-n_i}{\tau_n + \tau_p}$$

# High frequency response in MOS-C

Low Frequency

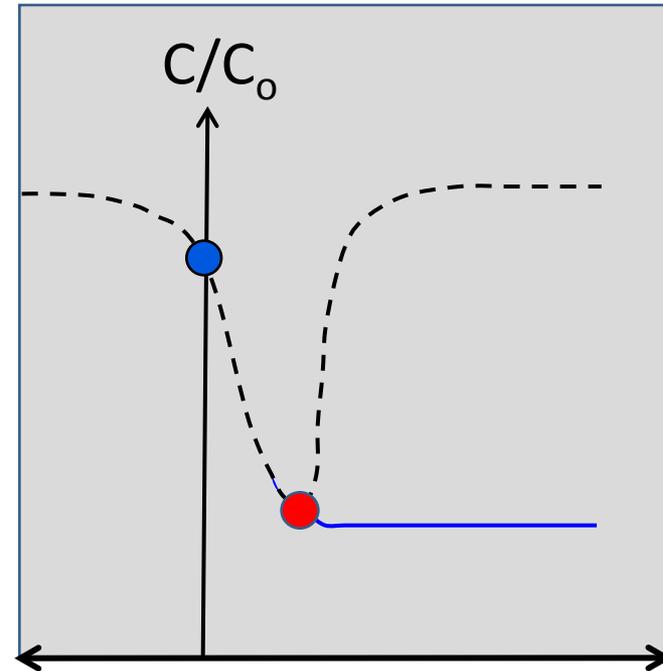
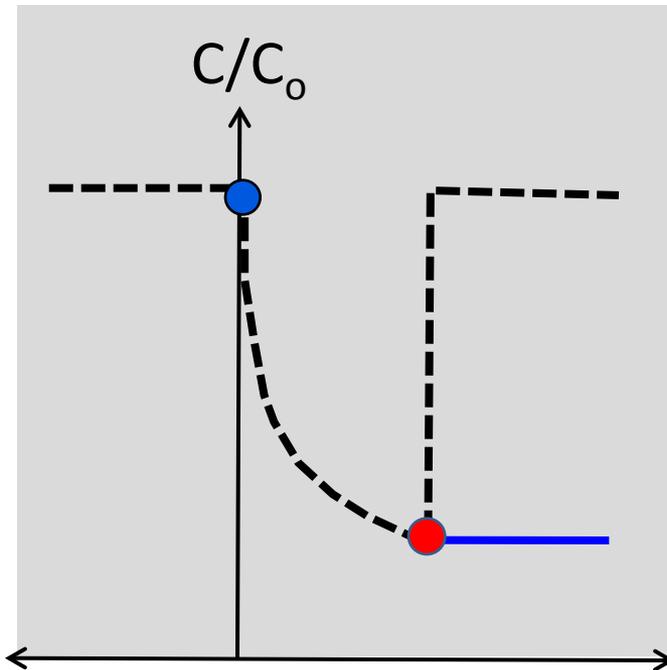


High Frequency



# Ideal vs. Real C-V Characteristics

Flat band voltage ...

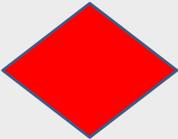


Threshold voltage ...

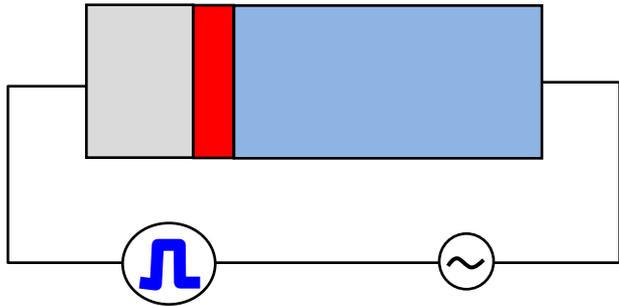
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# Topic Map

	Equilibrium	DC	Small signal	<b>Large Signal</b>	Circuits
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Schottky					
BJT/HBT					
<b>MOS</b>					

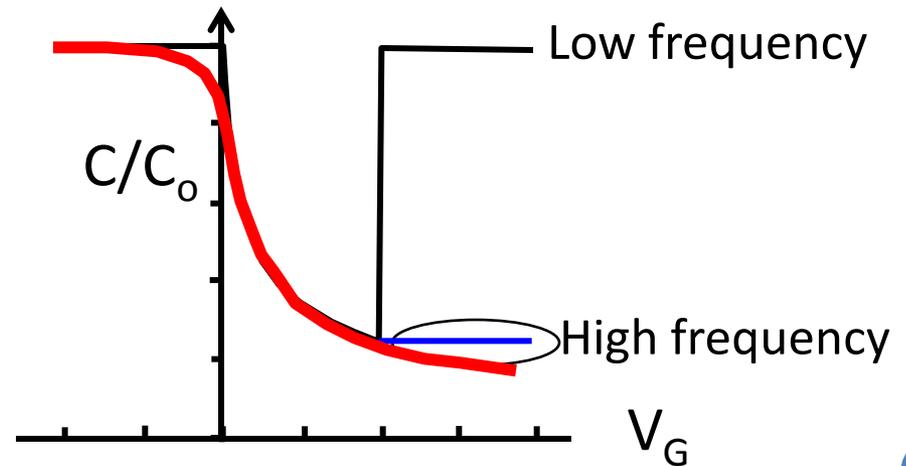
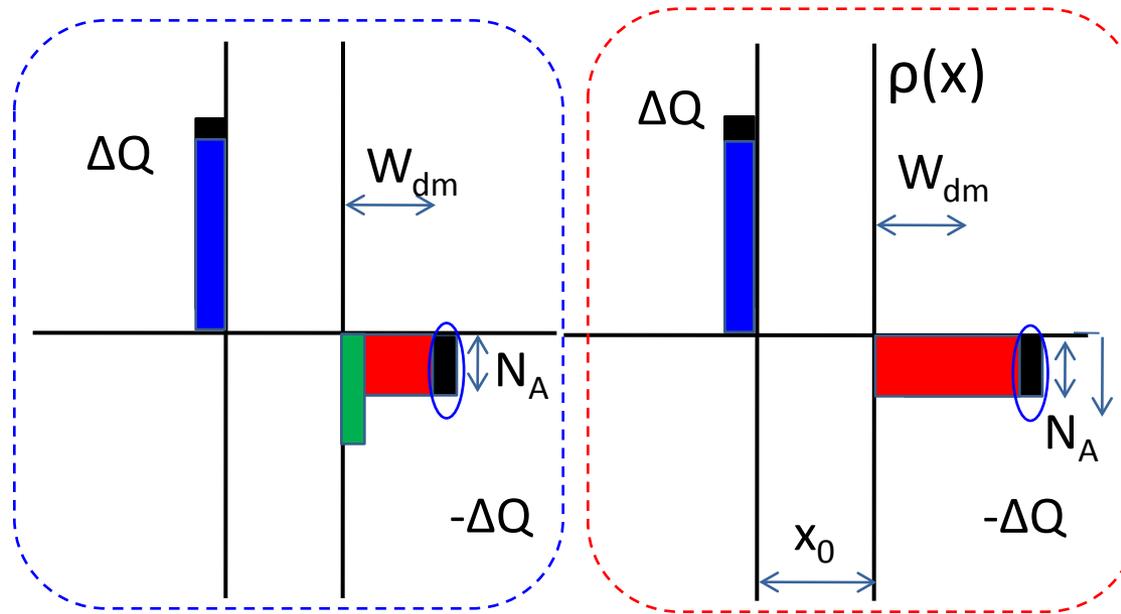
# Large Signal Deep Depletion



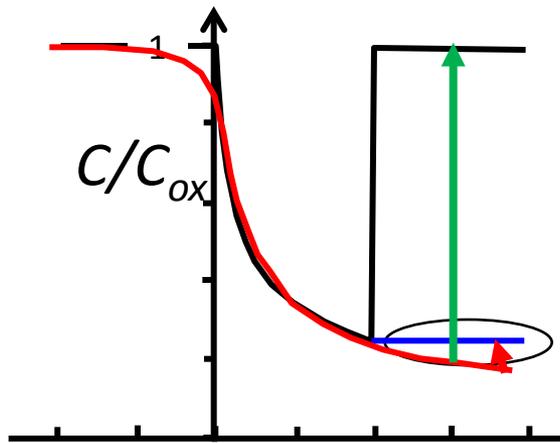
$$C_{j,dep} = \frac{C_0 C_s}{C_0 + C_s} = \frac{C_0}{1 + \frac{\kappa_{ox} W}{\kappa_s x_0}}$$

$$= \frac{C_0}{\sqrt{1 + \frac{V_G}{V_\delta}}}$$

**(even beyond threshold)**



# Relaxation from Deep Depletion

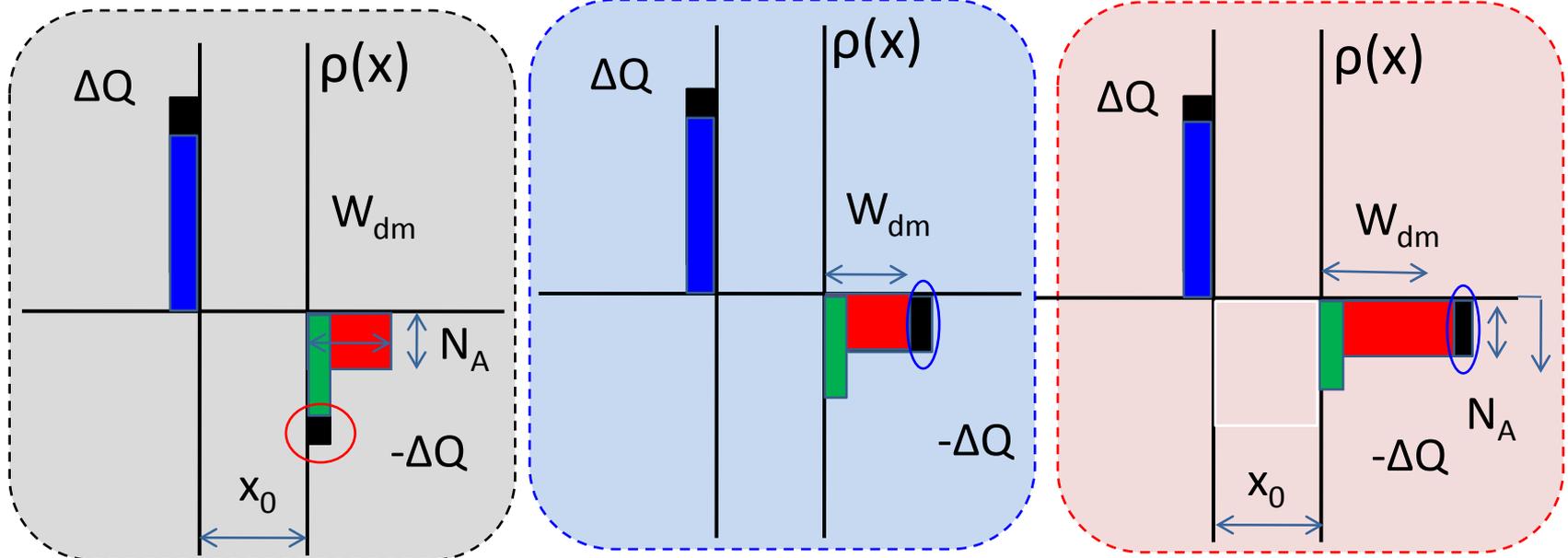


Low frequency

Depending on the measurement frequency, it will either merge with low-freq. or high-freq. curve.

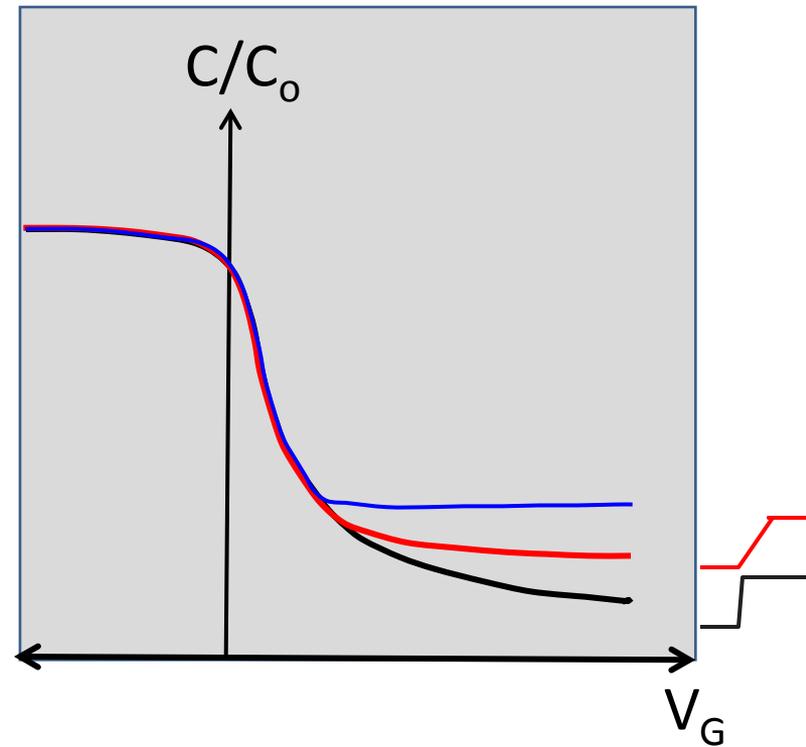
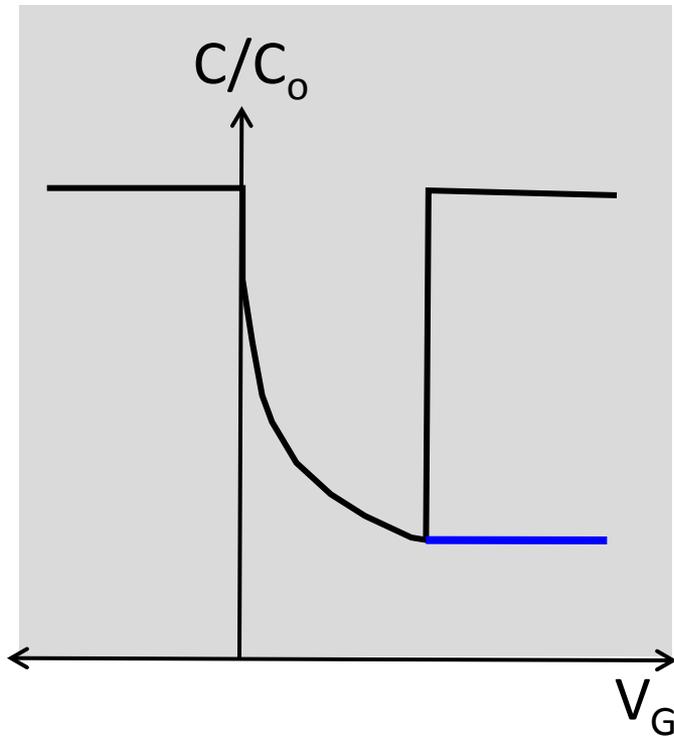
High frequency

Deep depletion



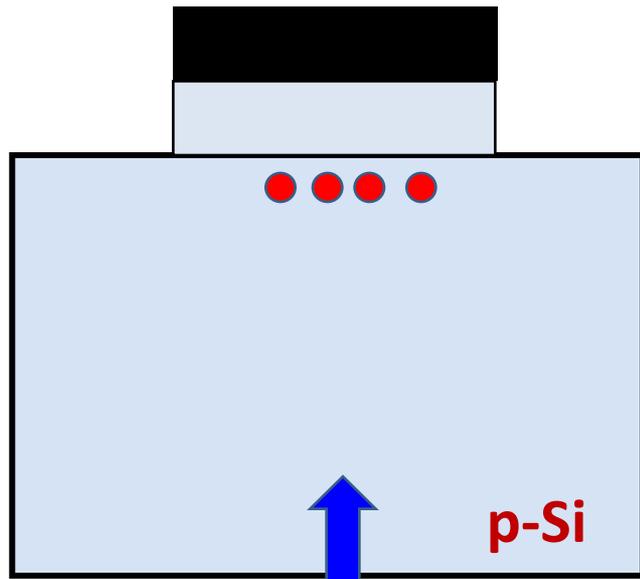
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Flat band voltage ...



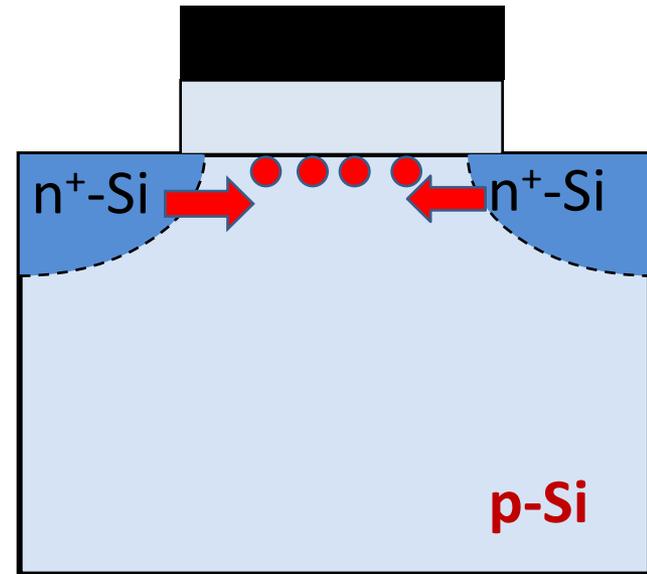
Threshold voltage ...

# Low or High frequency?



typically observe high-frequency CV

$$G = \frac{n_i}{2\tau}$$



typically observe low-frequency CV  
No deep-depletion as well

What happens if I shine light on a MOS capacitor?

# Summary

- 1) Since current flow through the oxide is small, we are primarily interested in the junction capacitance of the MOS-capacitor.
- 2) High frequency of MOS-C is very different than low-frequency C-V. In MOSFET, we only see low frequency response.
- 3) Deep depletion is an important consideration for MOS-capacitor that does not happen in MOSFETs.